

Amendments to the Specification:

Please amend the specification by inserting the paragraph below, after the title on page 1.

Cross-Reference to Related Application

This application claims priority based on International Patent Application No. PCT/FR2004/050377, entitled "Method for Producing Inclined Flank Patterns by Photolithography", filed on August 5, 2004 by Marc Rabarot, Mathieu Kipp and Christophe Kopp, which claims priority of French Application No. 03 50410, filed on August 7, 2003, and which was not published in English.